

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A coating apparatus that coats a substrate with a liquid material ~~on a substrate~~ in a coating chamber, comprising:

a first liquid supply system ~~provided~~ that supplies the liquid material to the coating chamber; and

a second liquid supply system ~~provided~~ that supplies a liquid to the first liquid supply system that cleans or that deactivates the liquid material remaining at least either in the coating chamber or in the first liquid supply system, wherein

the first liquid supply system includes:

a container that accumulates the liquid material;

a drip rate control section that controls a quantity of the liquid material that is drawn out from the container;

a nozzle section that discharges the liquid material; and

a liquid material pipe that all runs in a vertical direction without a horizontal portion relative to the vertical direction, and that connects each of the container, the drip rate control section, and nozzle section so that these sections are positioned in the vertical direction in this order from top to bottom.

2. (Original) The coating apparatus according to claim 1, further comprising a control mechanism provided with the coating chamber that controls an atmosphere in the coating chamber independently.

3. (Original) The coating apparatus according to claim 1, wherein a plurality of the second liquid supply systems are provided and at least one of the second liquid supply systems is a system that supplies a cleaning agent for cleaning the liquid material remaining at

least either in the coating chamber or first liquid supply system, and at least one other of the second liquid supply systems is a system that supplies a deactivation agent for deactivating the liquid material remaining at least either in the coating chamber or first liquid supply system.

4. (Original) The coating apparatus according to claim 1, wherein the coating chamber has a spin coater provided therein.

5. (Canceled)

6. (Original) The coating apparatus according to claim 1, wherein the coating chamber has a droplet discharge section provided therein that discharges micro droplets, and the droplet discharge section has a function of dripping micro droplets on a predetermined position on a substrate held on a stage by moving relatively to the stage holding the substrate.

7. (Original) The coating apparatus according to claim 1, wherein the coating chamber has a waste liquid collection mechanism provided therein that collects as waste liquid that is no longer necessary after having been introduced into the coating chamber.

8. (Canceled)

9. (Currently Amended) A thin film forming apparatus comprising:
a coating apparatus ~~according to claim 1~~ that coats a substrate with a liquid material in a coating chamber; and

a heat processing apparatus that heats a substrate on which a liquid material has been coated by the coating apparatus, wherein

the coating apparatus includes:

a first liquid supply system that supplies the liquid material to the coating chamber; and

a second liquid supply system that supplies a liquid to the first liquid supply system that cleans or that deactivates the liquid material remaining at least either in the coating chamber or in the first liquid supply system, and wherein

the coating apparatus and the heat processing apparatus are each provided with a control mechanism that controls an atmosphere in a processing chamber for processing the substrate independently for the coating apparatus and for the heat processing apparatus.

10. (Original) The thin film forming apparatus according to claim 9, further comprising a preprocessing apparatus that performs preprocessing such as cleaning a surface of the substrate, wherein the preprocessing apparatus is also provided with a control mechanism that controls independently an atmosphere in a processing chamber where processing of the preprocessing apparatus is performed.

11. (Original) The thin film forming apparatus according to claim 9, further comprising a connecting chamber that is connected to the processing chamber of each of the apparatuses, wherein the connecting chamber is also provided with a control mechanism that controls independently an atmosphere in the connecting chamber.

12-14. (Canceled)

15. (New) A coating apparatus that coats a substrate with a liquid material, comprising:

a coating chamber in which the substrate is disposed;

a first liquid supply system connected to the coating chamber and supplying the liquid material to the coating chamber;

a second liquid supply system connected to the coating chamber and supplying a deactivation agent for deactivating the liquid material to the coating chamber; and

a third liquid supply system connected to the coating chamber and supplying a cleaning agent for cleaning to the coating chamber.

16. (New) The coating apparatus according to claim 15, further comprising a control mechanism provided with the coating chamber that controls an atmosphere in the coating chamber independently.

17. (New) The coating apparatus according to claim 15, wherein the deactivation agent supplied from the second liquid supply system deactivates the liquid material remaining at least either in the coating chamber or first liquid supply system, and the cleaning agent supplied from the third liquid supply system cleans the liquid material remaining at least either in the coating chamber or first liquid supply system.

18. (New) The coating apparatus according to claim 15, wherein the coating chamber has a spin coater provided therein.

19. (New) The coating apparatus according to claim 15, wherein the first liquid supply system includes:

a container that accumulates the liquid material;

a drip rate control section that controls a quantity of the liquid material that is drawn out from the container;

a nozzle section that discharges the liquid material; and

a liquid material pipe that all runs in a vertical direction without a horizontal portion relative to the vertical direction, and that connects each of the container, the drip rate control section, and nozzle section so that these sections are positioned in the vertical direction in this order from top to bottom.

20. (New) The coating apparatus according to claim 15, wherein the coating chamber has a droplet discharge section provided therein that discharges micro droplets, and the droplet discharge section has a function of dripping micro droplets on a predetermined position on a substrate held on a stage by moving relatively to the stage holding the substrate.

21. (New) The coating apparatus according to claim 15, wherein the coating chamber has a waste liquid collection mechanism provided therein that collects as waste liquid that is no longer necessary after having been introduced into the coating chamber.

22. (New) The coating apparatus according to claim 15, wherein the liquid material includes cyclosilane or high order silane, and the deactivation agent includes isopropanol.

23. (New) The coating apparatus according to claim 15, wherein the liquid material includes cyclosilane or high order silane, and the deactivation agent includes tetramethyl ammonium hydroxide.

24. (New) The coating apparatus according to claim 19, wherein the deactivation agent is supplied from the second liquid supply system to the coating chamber via at least a part of the liquid material pipe through which the liquid material flows.

25. (New) The coating apparatus according to claim 19, wherein the cleaning agent is supplied from the third liquid supply system to the coating chamber via at least a part of the liquid material pipe through which the liquid material flows.